



IPW

Docket No.: 0171-1079PUS1  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Hiroki YOSHIKAWA et al.

Application No.: 10/811,924

Confirmation No.: 3156

Filed: March 30, 2004

Art Unit: 1756

For: PHOTOMASK BLANK, PHOTOMASK, AND  
METHOD OF MANUFACTURE

Examiner: S. D. Rosasco

**STATUS INQUIRY**


Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

It is respectfully requested that the attorney named below be advised of the status of the above-identified application. Please advise us of when we might expect to receive an Office Action from the Patent and Trademark Office.

Dated: JAN 31 2006

Respectfully submitted,

By  #42-874  
Gerald M. Murphy, Jr.  
Registration No.: 28,977  
BIRCH, STEWART, KOLASCH & BIRCH, LLP  
8110 Gatehouse Road  
Suite 100 East  
P.O. Box 747  
Falls Church, Virginia 22040-0747  
(703) 205-8000  
Attorney for Applicant